CHICAGO OFFICE TELEPHONE: 312/876-8000

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CONTINUED PROSECUTION APPLICATION (CPA) REQUEST TRANSMITTAL

(Only for Continuation or Divisional Applications under 37 CFR 1.53(d))

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Address to: Assistant Commissioner for Patents	Attorney Docket No.	Old Docket No. P97,0322 New No. 09794353-0005	
Box CPA Washington DC 20231	First Named Inventor	Mitsuhiro Nakamura	2
•	Express Mail Label No.	EL834557024US	
	Date:	November 12, 2001	100
This is a request for a X continuation (continued prosecution application (CPA)) of prior application num	ber <u>08/809,463</u> , filed on	7000 C

(continued prosecution application (CPA)) of prior application number ____08/809,463 July 18, 1997, entitled "MULTILAYERED STRUCTURE FOR FABRICATING AN OHMIC ELECTRODE AND OHMIC ELECTRODE"

1.		Enter the unentered Amendmentpreviously mailed on, under	37 CFR 1.116 in
		the prior non-provisional application.	
2.	<u>X</u>	Preliminary Amendment attached.	
3.		This application is filed by fewer than all the inventors named in the pr 37 CFR 1.53(d)(4).	ior application,
	a.	DELETE the following inventor(s) named in the prior non-proapplication:	ovisional
	b.	The inventor(s) to be deleted are set forth on a separate sheet a	ttached hereto.
4.		A new power of attorney or authorization of agent (PTO/SB/81) is enc	
5.	Inform	nation Disclosure Statement (IDS) is enclosed:	Ö
	a.	PTO-1449	<i>N</i>
	b.	Copies of IDS Citations	8 =

CLAIMS AS	FILED				== Co ::
	(1) FOR	(2) NUMBER FILED	(3) NUMBER EXTRA	(4) RATE	(5) BASIC FEE S\$740.00
	TOTAL CLAIMS	19		18.00	0.00
	CLAIMS				
	INDEPENDENT CLAIMS	5	2	84.00	168.00
	·	ANY MULTIPLE DEPENDENT CLAIMS? ()YES (X)NO		·	\$0.00 TE(
				TOTAL FILING FEE ->	HASOLOG SOLOG

01/28/2002 AWDNDAF1 00000104 08809463

01 FC:131 02 FC:102

740.00 OP 168.00 DP

6. Sma	all entity	status:
	a	A small entity statement is enclosed
	b	A small entity statement was filed in the prior non-provisional application and such status is still proper and desired.
•	c	Is no longer claimed.
7.	X any ov enclos	The Commissioner is hereby authorized to charge any additional fees or credit erpayment to Deposit Account No. 19-3140. A duplicate copy of this sheet is ed.
8.	<u>X</u>	A check in the amount of \$908.00 to cover the base filing fee is enclosed.
9.	_	Other: An Extension of Time to File Response to Office Action ofbe extended for month(s) to A check in the amount of \$ to cover the three-month extension fee is enclosed.
10.		The Commissioner is hereby authorized to charge the amount of \$ to cover the -month extension fee to Deposit Account No. 19-3140. A duplicate copy of this sheet is enclosed for that purpose.
		Respectfully submitted,
Nave	h 1	By: P. P. (Reg. 45,034) Christopher P. Rauch SONNENSCHEIN NATH & ROSENTHAL P.O. Box #061080 Wacker Drive Station, Sears Tower Chicago, IL 60606-1080 Telephone 312/876-8000 Customer ID #26263
Nove	ember 12	2, 2001
		re: this application 2) 876-8000 Ext 2606

#30/AMH73

IN THE WITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS:

Mitsuhiro Nakamura et al.

OLD DOCKET NO.: P97,0322

NEW DOCKET NO.: 09794353,0005

SERIAL NO.

08/809,463

GROUP ART UNIT: 2814

FILING DATE:

July 18, 1997

EXAMINER:

P. Cao

INVENTION:

"MULTI-LAYERED STRUCTURE FOR FABRICATING AN

OHMIC ELECTRODE AND OHMIC ELECTRODE"

PRELIMINARY AMENDMENT ACCOMPANYING CONTINUED PROSECUTION APPLICATION (CPA)

Hon. Assistant Commissioner for Patents Washington, DC 20231

SIR:

This Preliminary Amendment accompanies a Continued Prosecution Application (CPA) and is filed in response to the Decision on Request for Rehearing of September 13, 2001. In the Decision on Request for Rehearing, the Board of Patent Appeals and Interferences granted the Applicants' request for a rehearing, yet affirmed their earlier Decision on Appeal to maintain the Examiner's final rejection of the claims.

Please enter the following amendment prior to examination of the above-identified Continued Prosecution Application (CPA).

IN THE CLAIMS

Please amend claims 1, 9, 10, and 19 as follows:

Sy Sy

1. (Twice Amended) A multi-layered structure for fabricating an ohmic electrode, comprising a non-single crystal semiconductor layer comprising In and a film including at least a metal nitride film which are sequentially stacked on a III-V compound semiconductor body, wherein said metal nitride film is selected from the group consisting of a WN film, a WSiN film, a TaN film, a TaSiN film, a TiSiN film, and a TiON film.

